

XFEL0、最近の話題

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ERLビームダイナミクスWG

3次高調波によるXFELO

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PHYSICAL REVIEW LETTERS

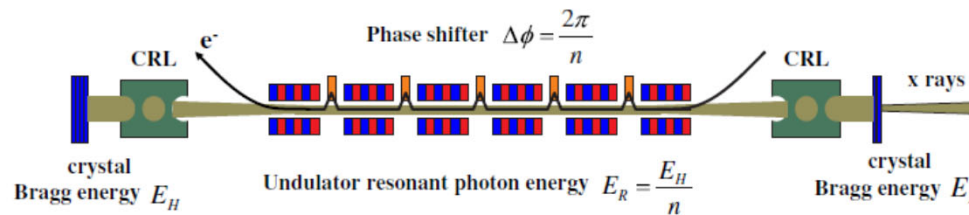
week ending
20 JANUARY 2012

Proposal for an X-Ray Free Electron Laser Oscillator with Intermediate Energy Electron Beam

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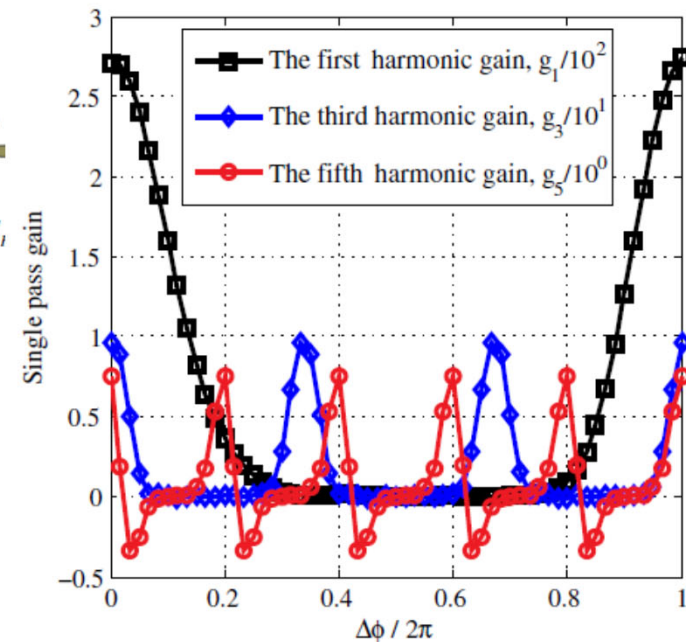
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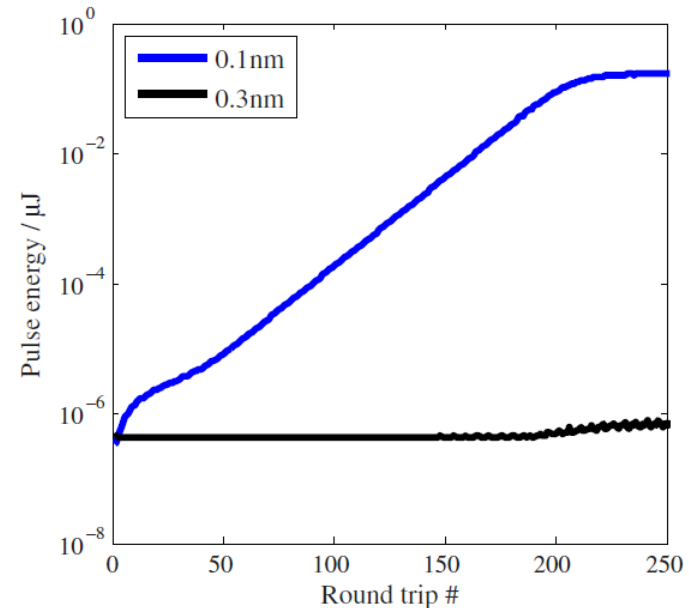
3.5 GeV electron で 12keV のXFELO を発振

アンジュレータ間の位相シフトで基本波の発振を抑制し、3次高調波のみを発振する



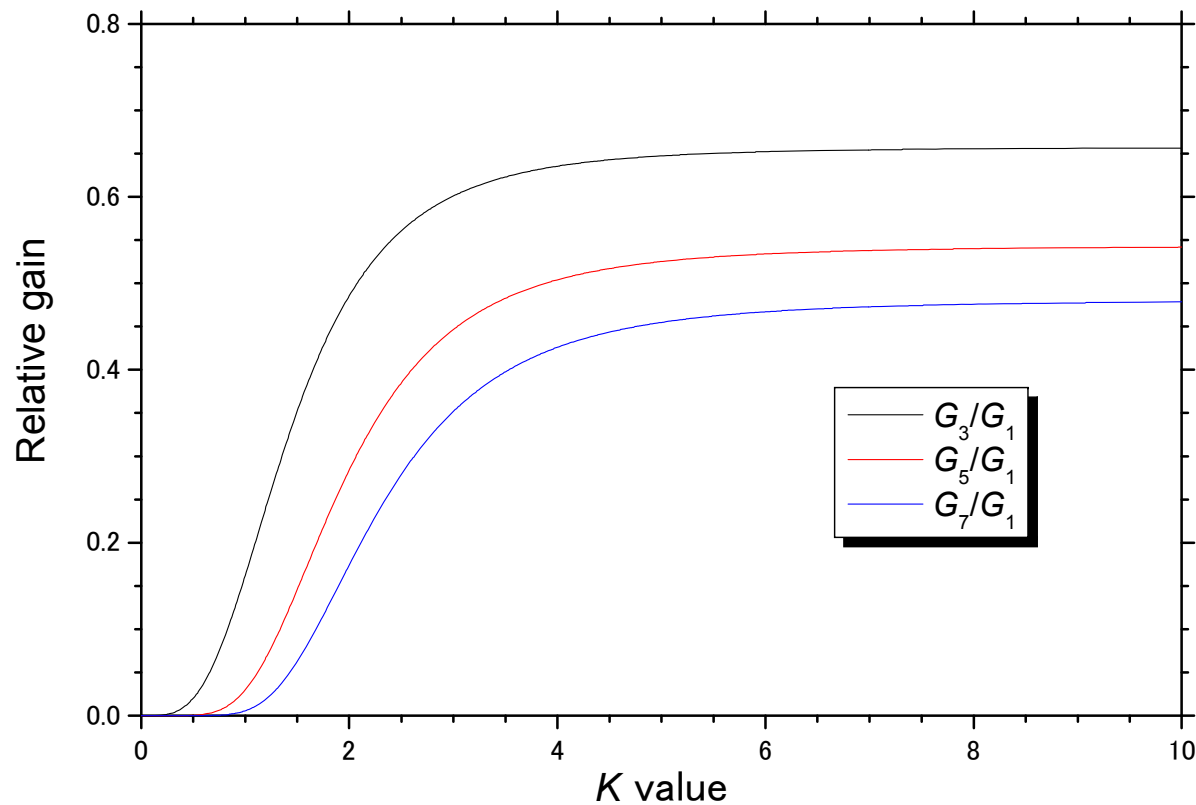
3次高調波によるXFEL

Parameters	Third harmonic	Fifth harmonic
Crystal Bragg energy E_H	12.42 keV	20.71 keV
Phase jump $\Delta\varphi$	$4\pi/3$	$6\pi/5$
Undulator period λ_u	15 mm	15 mm
Undulator number N_u	1200	1200
Undulator parameter K	1.3244	1.3244
Beam energy E	3.5 GeV	3.5 GeV
Slice energy spread σ	100 keV	100 keV
Beam peak current I	20 A	100 A
Slice emittance ε_n	$0.083 \mu\text{m-rad}$	$0.083 \mu\text{m-rad}$
Single-pass gain g_h	65%	72%
Total cavity reflection r	80%	80%
Cavity length L_c	150 m	150 m
Bragg crystal	C(4,4,4)	C(5,5,9)
FWHM spectral width	5.5 meV	24.6 meV
FWHM temporal width	463 fs	107 fs
Photons/pulse	0.86×10^8	0.24×10^8
Output peak power	0.35 MW	0.74 MW



高調波のゲイン計算

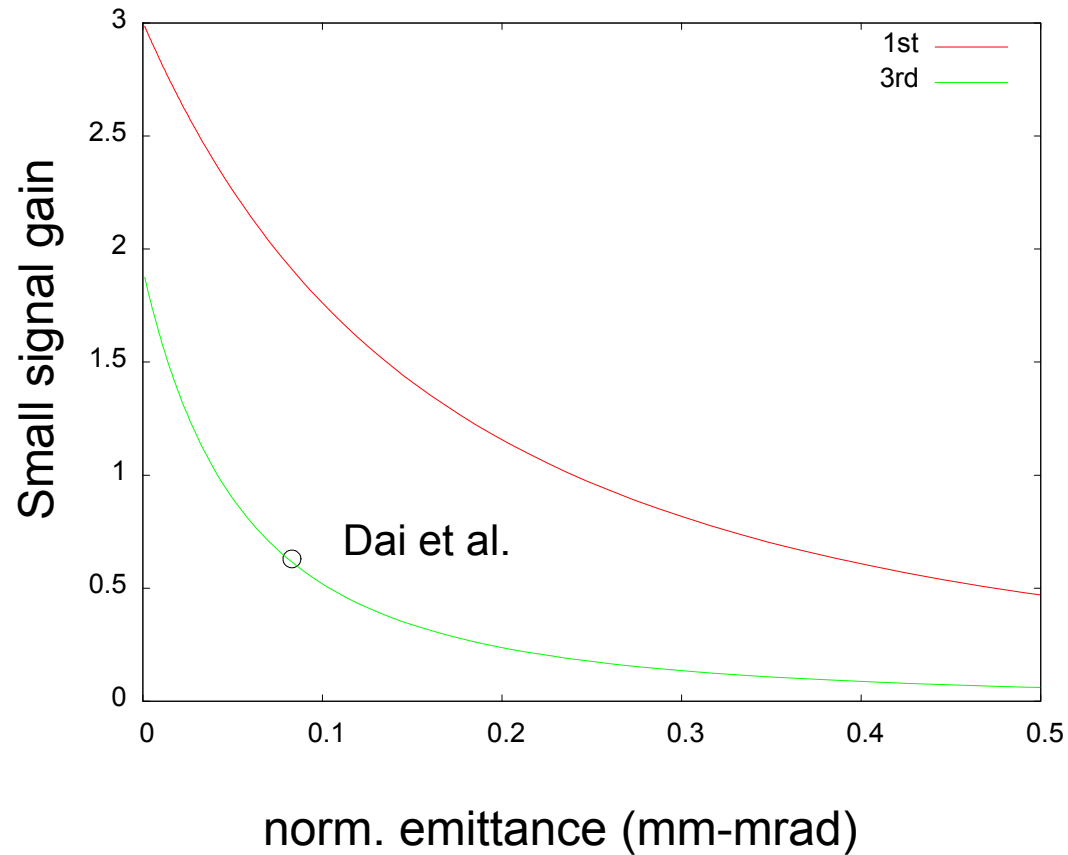
産総研、清さんによる



$$G_n = n \frac{[JJ]_n^2}{[JJ]_1^2} G_1$$

Filling factor (エミッタンス)、
エネルギー広がり効果を
別途加える。

解析式によるゲインの確認



beta = 20m とすると
Dai et al. 論文のゲインを
ほぼ再現した。

	Kim et al.	Hajima et al.	Dai et al.
E (GeV)	7	5	3.5
ϵ_n (mm-mrad)	0.082	0.13	0.083
σ_E (keV)	1400	250	100
charge	19	7.7	20
σ_t (ps)	2	0.38	(0.40)
I_p (A)	-	-	20
Undulator pitch (mm)	18.8	14.3	15
Undulator period	3000	3000	1200
Undulator K	1.414	0.8344	1.3244
*Gap (mm)	(5)	(5)	(3.25)
Gain (%)	26	40	65
X-ray Bandwidth (meV)	2.3	-	5.5
Length (fs)	850	510	463
Photon/pulse	10^9	0.7×10^8	0.86×10^8

すべて 12keV (1 Å)

*Gap → Halbach type を仮定したとき

K-J. Kim 氏からの問い合わせ

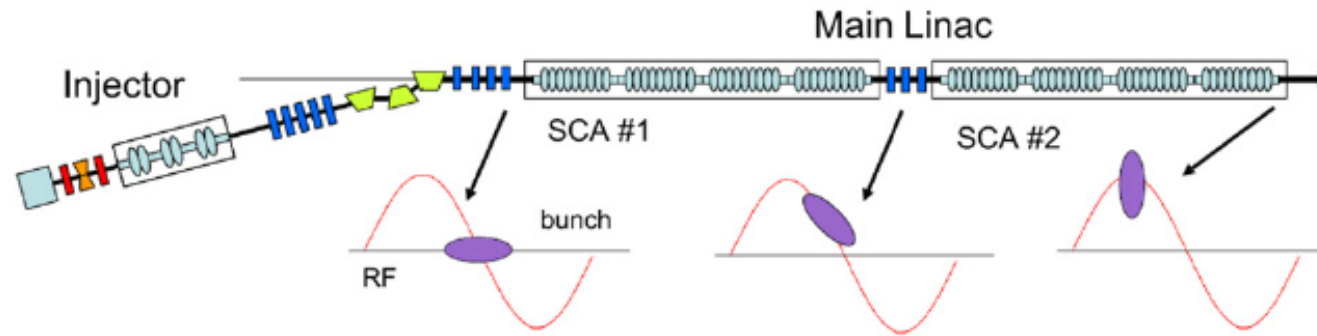
The question is whether you can produce and accelerate such beams. If yes, the beam is suitable for an XFEL, possibly with >100 MHz rep rate, with high average brightness.

Kwang-Je

- > the gain calculation I did was for our "nominal" beam and undulator parameters (E=7 GeV, Nu = 3000, etc.) with the following changes:
 - > Charge = 1.0 pC
 - > Length = 0.25 ps (I = 1.6 A)
 - > emittance = 0.062 mm*mrad [per Rosenzweig et. al.'s NIMA 593, 39 (2008)]
 - > energy spread = 100 keV
 - >
 - > I find that the gain is maximized at 0.5 when $Z_R = Z_{\beta} = 14$ m.
 - >
 - > If I increase the energy spread to 250 keV the gain is 0.4.

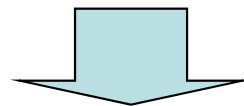
ERL injector and velocity bunching

R. Hajima et al. / Nuclear Instruments and Methods in Physics Research A 637 (2011) S37–S42



Parameters of electron bunch at the end of the main linac are bunch charge 7.7 pC, energy 27.7 MeV, rms bunch length $\sigma_t=380$ fs, rms energy spread $\sigma_E=250$ keV, rms normalized emittance $\varepsilon_x=0.16$ mm-mrad, and $\varepsilon_y=0.13$ mm-mrad. The energy

7.7 pC, 380 fs, 0.16 mm-mrad, 250 keV



??? 1 pC, 250 fs, 0.062 mm-mrad, 100 keV ???

ビームダイナミクス以外の検討=ビームモニタ?